	Application No.	Applicant(s)	
	10/771,808	CHUANG ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Chandra Chaudhari	2891	
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in or other appropriate communication is subsection of the communication is subsection in the communication in the communication is subsection.	this application. If not included nication will be mailed in due course	
1. X This communication is responsive to February 3, 2004.			
2. ⊠ The allowed claim(s) is/are <u>1-17 and 23</u> .			
3. $igspace$ The drawings filed on <u>03 February 2004</u> are accepted by the	ne Examiner.	•	
4. Acknowledgment is made of a claim for foreign priority unal All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have international Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give concluding changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date	been received. been received in Application cuments have been received of this communication to file at ENT of this application. itted. Note the attached EXALES reason(s) why the oath or out to be submitted. on's Patent Drawing Review as Amendment / Comment or it is Amendment / Comment or it is Af(c)) should be written on the header according to 37 CFR sit of BIOLOGICAL MATE	in this national stage application from this national stage application from this national stage application from the requirement of the complying with the requirement of the complying the complying the complying the complete complying the complete complete complying the complete complete complete complete complete complete complying the complete	ents E OF
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date Oct 21, 2004 4. ☐ Examiner's Comment Regarding Requirement for Deposit	6. ☐ Interview Sur Paper No./N 8), 7. ⊠ Examiner's A	ormal Patent Application (PTO-152) mmary (PTO-413), fail Date mendment/Comment statement of Reasons for Allowance	
of Biological Material	9. 🗌 Other		

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Restriction to one of the following inventions is required under 35 U.S.C. 121:

I. Claims 1-17 and 23 drawn to a method of making a semiconductor device, classified

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in class 438, subclass 270.

II. Claims 18-22, drawn to a semiconductor device, classified in class 257, subclass 331.

The inventions are distinct, each from the other because of the following reasons:

Inventions I and II are related as process of making and product made. The inventions are distinct if either or both of the following can be shown: (1) that the process as claimed can be used to make other and materially different product or (2) that the product as claimed can be made by another and materially different process (MPEP § 806.05(f)). In the instant case, the product as claimed can be made by another and materially different process such as using mechanical means instead of etching.

Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification, and the search required for Group I is not required for Group II, restriction for examination purposes as indicated is proper.

During a telephone conversation with Chun-Pok Leung on August 3, 2005 a provisional election was made without traverse to prosecute the invention of Group I, claims 1-17 and 23. Affirmation of this election must be made by applicant in replying to this Office action. Claims 18-22 are withdrawn from further consideration by the examiner, 37 CFR 1.142(b), as being drawn to a non-elected invention.

Applicant is reminded that upon the cancellation of claims to a non-elected invention, the inventorship must be amended in compliance with 37 CFR 1.48(b) if one or more of the currently

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named inventors is no longer an inventor of at least one claim remaining in the application. Any amendment of inventorship must be accompanied by a request under 37 CFR 1.48(b) and by the fee required under 37 CFR 1.17(i).

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Chun-Pok Leung on August 8, 2005.

The application has been amended as follows:

Cancel claims 18-22.

In claim 1, line 23, after "etching", insert --using a two-step etching process,--.

In claim 6, line 1, delete "o the", and insert --on the--.

In claim 10, line 1, delete "anisotropically etching", and insert -- the two-step etching process for--;

lines 2-3, delete "includes a two-step etching process which".

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In claim 15, line 14, delete "etching", and insert --anisotropically etching using a two-step etching process,--.

In claim 23, line 10, delete "etch", and insert --etching--;

line 15, delete "and then", and insert --, patterning and anisotropically etching the isolation layer and the gate oxide layer using a two-step etching process, and then forming--.

The following is an examiner's statement of reasons for allowance:

The prior art does not disclose forming sources in the body region by using the polysilicon plate as a mask, forming an isolation layer, patterning and anisotropically etching the isolation layer and the gate oxide layer using a two-step etching process as claimed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Any inquiry concerning this communication or earlier communications from the examiner

should be directed to Chandra Chaudhari whose telephone number is 571-272-1688. The examiner

can normally be reached on Mon - Fri (9:00-5:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Bill

Baumeister can be reached on 571-272-1722. The fax phone number for the organization where this

application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application

Information Retrieval (PAIR) system. Status information for published applications may be obtained

from either Private PAIR or Public PAIR. Status information for unpublished applications is available

through Private PAIR only. For more information about the PAIR system, see http://pair-

direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the

Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Chandra Chaudhari

Primary Examiner

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Chandra Chaudhari

August 8, 2005